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## (54) PROPYLENE RESIN COMPOSITION, AND MOLDED ARTICLE AND CONTAINER MADE FROM THE COMPOSITION

### (57)Abstract:

**PROBLEM TO BE SOLVED:** To obtain a composition excellent in transparency and rigidity while retaining high impact resistance even at low temperature, for example, at 0° C or lower, by adding a nucleating agent to a propylene resin which satisfies specified conditions based on measurements by the temperature-rise fractionation method.

**SOLUTION:** The propylene resin used is a propylene/ethylene block copolymer comprising mainly a propylene homopolymer and a propylene/ethylene copolymer and has specified physical property values. The amount of its component eluted at 30° C or lower, measured by the temperature-rise fractionation method, is 10-30 wt.% of the total elution amount and the ethylene content of the component is 10-25 wt.%. The amount of its component eluted in a temperature range from 40 to 85° C, measured by the temperature-rise fractionation method, is 13-75 wt.% of the total elution amount. The intrinsic viscosity  $[\eta]_1$  of the component eluted at 103° C or higher and the intrinsic viscosity  $[\eta]_2$  of the component eluted at 30° C or lower, obtained by the temperature-rise fractionation method, satisfy the relation of the formula:  $4/3.[\eta]_1 > [\eta]_2$ .

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